Section I. (The Claims)

Please amend claims 1, 4 and 8, and cancel claim 3, as set out below in the listing of claims 1-59 of the application.

- 1. (Currently Amended) A cleaning composition including an active cleaning combination (ACC), wherein said ACC selected from the group consisting consists of: (a) a quaternary base in combination with at least one of alkali and alkaline earth base; and (b) a strong base in combination with an oxidant, wherein and said cleaning composition is useful for removing photoresist and/or sacrificial anti-reflective coating (SARC) materials from a substrate having such material(s) thereon.
- 2. (Original) The cleaning composition of claim 1, which is devoid of hydroxylamine therein.
- 3. (Cancelled)
- 4. (Currently Amended) The cleaning composition of claim $\underline{1}$ [[3]], comprising the following components:
 - 0.1 40.0 weight % organic quaternary base;
 - 0.01-5 weight % alkali or alkaline earth base;
 - 0-80 weight % solvent(s) and/or amine(s);
 - 0-5 weight % surfactant;
 - 0 10 weight % chelator/passivation agent; and
 - 0-98 weight % water,

wherein percentages of the components are percentages by weight, based on total weight of the composition, and wherein the total of the weight percentages of such components of the composition does not exceed 100 weight %.

- 5. (Previously Presented) The cleaning composition of claim 1, including at least one additional ingredient selected from the group consisting of stabilizers, dispersants, anti-oxidants, fillers, penetration agents, adjuvants, additives, and excipients.
- 6. (Original) The cleaning composition of claim 3, comprising the following components:

- 2-15 weight % organic quaternary base;
- ~0.01-2 weight % alkali or alkaline earth base;
- 0-50 weight % solvent(s) and/or amine(s);
- ~0.01-2 weight % surfactant;
- 0-5 weight % chelator/passivation agent; and
- 40 95 weight % water,

wherein percentages of the components are percentages by weight, based on total weight of the composition, and wherein the total of the weight percentages of such components of the composition does not exceed 100 weight %.

7. (Previously Presented) A cleaning composition selected from the group consisting of Formulations A-C², wherein all percentages are by weight, based on the total weight of the formulation:

Formulation A

- 5.36% benzyltrimethylammonium hydroxide
- 0.28% potassium hydroxide
- 3.0% 4-methylmorpholine N-oxide
- 0.30% polyoxyethylene(150) dinonylphenyl ether
- 0.08% 2-mercaptobenzimidazole
- 91.0% water

Formulation B

- 5.36% benzyltrimethylammonium hydroxide
- 0.28% potassium hydroxide
- 3.0% 4-methylmorpholine N-oxide
- 0.30% polyoxyethylene(150) dinonylphenyl ether
- 0.20% 5-amino-1,3,4-thiadiazole-2-thiol
- 90.86% water

Formulation C

- 3.60% benzyltrimethylammonium hydroxide
- 0.27% potassium hydroxide
- 3.5% 4-methylmorpholine N-oxide
- 15.0% 4-(3-aminopropyl)morpholine
- 0.30% polyoxyethylene(150) dinonylphenyl ether
- 0.08% 2-mercaptobenzimidazole
- 77.25% water

Formulation D

5.36% benzyltrimethylammonium hydroxide

0.28% potassium hydroxide

20.0% dimethyl sulfoxide

0.08% 2-mercaptobenzimidazole

74.28% water

Formulation E

5.36% benzyltrimethylammonium hydroxide

0.28% potassium hydroxide

10.0% tetramethylene sulfone

0.30% oxirane, methyl-, polymer with oxirane, ether with 2,2'-(oxidoimino)bis(ethanol) (2:1), N(-3(C9-11-isoalkyloxy)propyl)derivatives, C₁₀-rich

0.08% 2-mercaptobenzimidazole

83.98% water

Formulation F

5.36% benzyltrimethylammonium hydroxide

0.28% potassium hydroxide

10.0% di(ethyleneglycol)butyl ether

10.0% 2-(2-dimethylamino)ethoxy)ethanol

0.30% oxirane, methyl-, polymer with oxirane, ether with 2,2'-(oxidoimino)bis(ethanol) (2:1), N(-3(C9-11-isoalkyloxy)propyl)derivatives, C₁₀-rich

74.06% water

Formulation G

5.36% benzyltrimethylammonium hydroxide

0.28% potassium hydroxide

10.0% tetramethylene sulfone

10.0% di(ethyleneglycol)butyl ether

0.10% oxirane, methyl-, polymer with oxirane, mono(octylphenyl)ether

0.08% 2-mercaptobenzimidazole

74.18% water,

Formulation H

benzyltrimethylammonium hydroxide, 40% aqueous solution	9.0 %
potassium hydroxide, 45% aqueous solution	0.6 %
N-methylmorpholine oxide, 50% aqueous solution	7.0 %
dinonylphenol ethoxylate, 7% aqueous solution	4.3 %
2-mercaptobenzimidazole	0.1 %
aminopropylmorpholine	20.0 %
water	59.02 %

Formulation I

benzyltrimethylammonium hydroxide, 40% aqueous solution	9.0 %
potassium hydroxide, 45% aqueous solution	0.6 %
N-methylmorpholine oxide, 50% aqueous solution	7.0 %

dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	4.3 % 0.1 % 15.0 % 64.02 %
Formulation J	
benzyltrimethylammonium hydroxide, 40% aqueous solution potassium hydroxide, 45% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	9.0 % 0.6 % 7.0 % 4.3 % 0.1 % 10.0 % 69.02 %
Formulation K	
benzyltrimethylammonium hydroxide, 40% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	13.4 % 7.0 % 0.6 % 0.08 % 0.3 % 78.62 %
Formulation L	
benzyltrimethylammonium hydroxide, 40% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	13.4 % 7.0 % 1.2 % 0.08 % 0.3 % 78.02 %
Formulation M	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	5.85 % 7.0 % 1.2 % 0.08 % 0.3 % 85.57 %
Formulation N	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	2.93 % 7.0 % 1.2 % 0.08 % 0.3 % 88.49 %

0.6 % 0.08 %

2.33 %

Formulation O benzyltrimethylammonium hydroxide, 40% aqueous solution 7.2 % N-methylmorpholine oxide, 50% aqueous solution 7.0 % 0.6 % KOH, 45% aqueous solution 2-mercaptobenzimidizole 0.08 % 0.3 % dinonylphenol polyoxyethylene 84.82 % water Formulation P benzyltrimethylammonium hydroxide, 40% aqueous solution 3.6 % 7.0 % N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 1.2 % 0.08 % 2-mercaptobenzimidizole dinonylphenol polyoxyethylene 0.3 % 87.82 % water Formulation Q 3.6 % benzyltrimethylammonium hydroxide, 40% aqueous solution N-methylmorpholine oxide, 50% aqueous solution 7.0 % 0.6 % KOH, 45% aqueous solution 0.08 % 2-mercaptobenzimidizole 0.3 % dinonylphenol polyoxyethylene 88.42 % water Formulation R benzyltrimethylammonium hydroxide, 40% aqueous solution 7.2 % 7.0 % N-methylmorpholine oxide, 50% aqueous solution 0.3 % KOH, 45% aqueous solution 0.08 % 2-mercaptobenzimidizole 0.3 % dinonylphenol polyoxyethylene water 85.12 %, Formulation S benzyltrimethylammonium hydroxide, 40% aqueous solution 22.26 % 0.6 % Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole 0.08 % methyldiethanolamine 2.33 % 1.69 % phosphoric acid (86 %) 3-amino-5-mercapto-1,2,4-triazole 1.0 % 72.04 % water Formulation T benzyltrimethylammonium hydroxide, 40% aqueous solution 22.26 %

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Potassium hydroxide, 45% aqueous solution

2-mercaptobenzimidazole methyldiethanolamine

phosphoric acid (86 %) 4-methyl-2-phenyl-imidazole water	1.69 % 1.0 % 72.04 %
Formulation U	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) 2-mercaptothiazoline water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation V	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) 8-hydroxyquinoline water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation W	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) 1-phenyl-2-tetrazoline-5-thione water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation X	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) gallic acid water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation Y	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) salicylic acid water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %

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Formulation Z	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) ascorbic acid water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation A ²	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole aminopropyl morpholine 4-methyl-2-phenyl-imidazole water	7.2 % 0.6 % 0.08 % 10 % 1.0 % 81.12 %
Formulation B ²	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole aminopropyl morpholine 4-methyl-2-phenyl-imidazole water	7.2 % 0.6 % 0.08 % 10 % 0.5 % 81.62 %
Formulation C ²	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole aminopropyl morpholine 4-methyl-2-phenyl-imidazole water	7.2 % 0.6 % 0.08 % 10 % 1.0 % 81.02 %

wherein said cleaning composition is useful for removing photoresist and/or sacrificial antireflective coating (SARC) materials from a substrate having such material(s) thereon.

0.1 %

8. (Withdrawn) The eleaning composition of claim 1, wherein said ACC comprises (b) A cleaning composition including an active cleaning combination (ACC) consisting of a strong base in combination with an oxidant, wherein said cleaning composition is useful for removing photoresist and/or sacrificial anti-reflective coating (SARC) materials from a substrate having such material(s) thereon.

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dinonylphenol polyoxyethylene

- 9. (Withdrawn) The cleaning composition of claim 8, which includes an aqueous solution of at least one oxidant, a strong base, optionally a chelator and optionally a co-solvent and/or a surfactant.
- 10. (Original) The cleaning composition of claim 1, wherein the ACC comprises potassium hydroxide.
- 11. (Withdrawn) The cleaning composition of claim 8, including the following components:
 - 0.1-30 wt % strong base;
 - 0.01-30 wt % oxidant;
 - 0-10 wt % chelator;
 - 0-5 wt % surfactant;
 - 0-50 wt % co-solvent; and
 - 20-98.9 wt % deionized water,

wherein percentages of the components are percentages by weight, based on total weight of the composition, and wherein the total of the weight percentages of such components of the composition does not exceed 100 weight %.

- 12. (Withdrawn) The cleaning composition of claim 11, wherein the strong base comprises a base species selected from the group consisting of potassium hydroxide and alkylammonium hydroxides and choline hydroxide.
- 13. (Withdrawn) The cleaning composition of claim 8, wherein the oxidant comprises an oxidant species selected from the group consisting of hydrogen peroxide, amine-N-oxides, perborate salts, persulfate salts, and combinations of two or more of the foregoing.
- 14. (Previously Presented) The cleaning composition of claim 1, further comprising a chelator.
- 15. (Original) The cleaning composition of claim 14, wherein the chelator comprises a chelator species selected from the group consisting of: triazoles; triazoles substituted with substituent(s) selected from the group consisting of C₁-C₈ alkyl, amino, thiol, mercapto, imino, carboxy and nitro; thiazoles; tetrazoles; imidazoles; phosphates; thiols; azines; glycerols; amino acids; carboxylic acids; alcohols; amides; and quinolines.

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- 16. (Original) The cleaning composition of claim 14, wherein the chelator comprises a chelator species selected from the group consisting of: 1,2,4-triazole; benzotriazole; tolyltriazole; 5-phenyl-benzotriazole; 5-nitro-benzotriazole; 1-amino-1,2,4-triazole; hydroxybenzotriazole; 2-(5-amino-pentyl)-benzotriazole; 1-amino-1,2,3-triazole; 1-amino-5-methyl-1,2,3-triazole; 3-3-mercapto-1,2,4-triazole; 3-isopropyl-1,2,4-triazole; 5-phenylthiolamino-1,2,4-triazole; benzotriazole; halo-benzotriazoles wherein halo is selected from the group consisting of F, Cl, Br and I: naphthotriazole; 2-mercaptobenzoimidizole; 2-mercaptobenzothiazole; 5-aminotetrazole; 2,4-diamino-6-methyl-1,3,5-triazine; 5-amino-1,3,4-thiadiazole-2-thiol; thiazole: triazine; methyltetrazole; 1,3-dimethyl-2-imidazolidinone; 1,5-pentamethylenetetrazole; 1-phenyl-5diaminomethyltriazine; mercaptobenzothiazole; imidazoline thione; mercaptotetrazole; mercaptobenzimidazole; 4-methyl-4H-1,2,4-triazole-3-thiol; 5-amino-1,3,4-thiadiazole-2-thiol; benzothiazole; trritolyl phosphate; indiazole; guanine; adenine; glycerol; thioglycerol; nitrilotriacetic acid; salicylamide; iminodiacetic acid; benzoguanamine; melamine; thiocyranuric acid; anthranilic acid; 8-hydroxyquinoline; 5-carboxylic acid-benzotriazole; 3-mercaptopropanol; boric acid; and iminodiacetic acid.
- 17. (Previously Presented) The composition of claim 1, further comprising a surfactant.
- 18. (Original) The composition of claim 17, wherein the surfactant comprises a surfactant species selected from the group consisting of: fluoroalkyl surfactants; polyethylene glycols; polypropylene glycols; polyethylene glycol ethers; polypropylene glycol ethers; carboxylic acid salts; dodecylbenzenesulfonic acid and salts thereof; polyacrylate polymers; dinonylphenyl polyoxyethylene; silicone polymers; modified silicone polymers; acetylenic diols; modified acetylenic diols, alkylammonium salts; modified alkylammonium salts; and combinations of two or more of the foregoing.
- 19. (Previously Presented) The composition of claim 1, further comprising a co-solvent.
- 20. (Original) The composition of claim 19, wherein the co-solvent comprises a co-solvent species selected from the group consisting of: amines; glycols; glycol ethers; polyglycol ethers; and combinations of two or more of the foregoing.
- 21. (Withdrawn) The composition of claim 19, wherein the co-solvent comprises a co-solvent

dimethyldiglycolamine; 1,8selected from group consisting of: species the diazabicyclo[5.4.0]undecene; aminopropylmorpholine; triethanolamine; methylethanolamine; propylene glycol; neopentyl glycol; hydroxyethylmorpholine; diethylene glycol; aminopropylmorpholine; di(ethylene glycol)monoethyl ether; di(propylene glycol)propyl ether; ethylene glycol phenyl ether; di(propylene glycol) butyl ether; butyl carbitol; polyglycol ethers; and combinations of two or more of the foregoing.

- 22. (Withdrawn) The cleaning composition of claim 8, including:
 - 0.1-30 wt % strong base
 - 2-30 wt % oxidant
 - 0-10 wt % chelator
 - 0-5 wt % surfactant
 - 20-98 wt % deionized water

wherein percentages of the components are percentages by weight, based on total weight of the composition, and wherein the total of the weight percentages of such components of the composition does not exceed 100 weight %.

23. (Withdrawn) The cleaning composition of claim 1, selected from the group consisting of Formulations D²-R², wherein all percentages are by weight, based on the total weight of the formulation:

Formulation D²

tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 3-amino-5-mercapto-1,2,4-triazole water	14.7 % 7.0 % 4.3 % 0.1 % 73.9 %
Formulation E ²	
tetramethylammonium hydroxide, 25% aqueous solution	14.7 %
N-methylmorpholine oxide, 50% aqueous solution	7.0 %
dinonylphenol ethoxylate, 7% aqueous solution	4.3 %
ammonium tetrathiomolybdate	0.1 %
water	73.9 %
Formulation F ²	•
tetramethylammonium hydroxide, 25% aqueous solution	14.7 %
N-methylmorpholine oxide, 50% aqueous solution	7.0 %

dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	4.3 % 0.1 % 20.0 % 53.9 %
Formulation G ² tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution	14.7 % 7.0 % 4.3 %
2-mercaptobenzimidazole N-ethylmorpholine water	0.1 % 20.0 % 53.9 %
Formulation H ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminoethylpiperidine water	14.7 % 7.0 % 4.3 % 0.1 % 20.0 % 53.9 %
Formulation I ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 3-amino-5-1,2,4-triazole aminopropylmorpholine water	14.7 % 7.0 % 4.3 % 0.1 % 20.0 % 53.9 %
Formulation J ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 3-amino-5-1,2,4-triazole aminopropylmorpholine water	14.7 % 7.0 % 4.3 % 0.1 % 10.0 % 63.9 %
Formulation K ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	14.7 % 7.0 % 4.3 % 0.1 % 20.0 % 53.9 %

Formulation L ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	14.7 % 7.0 % 4.3 % 0.1 % 10.0 % 63.9 %
Formulation M ²	
tetramethylammonium hydroxide, 25% aqueous solution hydrogen peroxide, 30% aqueous solution 5-aminotetrazole water	4.0 % 2.0 % 0.1 % 93.9 %
Formulation N ²	
tetramethylammonium hydroxide, 25% aqueous solution hydrogen peroxide, 30% aqueous solution 2,4-diamino-6-methyl-1,3,5-triazine water	4.0 % 2.0 % 0.1 % 93.9 %
Formulation O ²	
tetramethylammonium hydroxide, 25% aqueous solution hydrogen peroxide, 30% aqueous solution 5-amino-1,3,4-thiadiazole-2-thiol water	4.0 % 2.0 % 0.1 % 93.9 %
Formulation P ²	
tetramethylammonium hydroxide, 25% aqueous solution hydrogen peroxide, 30% aqueous solution 1,2,4-triazole water	4.0 % 2.0 % 0.1 % 93.9 %
Formulation Q ²	
tetramethylammonium hydroxide, 25% aqueous solution hydrogen peroxide, 30% aqueous solution 2,4-dihydroxy-6-methylpyrimidine water	4.0 % 2.0 % 0.1 % 93.9 %
Formulation R ²	
tetramethylammonium hydroxide, 25% aqueous solution. hydrogen peroxide, 30% aqueous solution 8-hydroxyquinoline water	4.0 % 2.0 % 0.1 % 93.9 %.

- 24. (Withdrawn) A method of removing photoresist and/or SARC material from a substrate having said material thereon, said method comprising contacting the substrate with a cleaning composition for sufficient time to at least partially remove said material from the substrate, wherein the cleaning composition includes an active cleaning combination (ACC) selected from the group consisting of: (a) a quaternary base in combination with at least one of alkali and alkaline earth base; and (b) a strong base in combination with an oxidant.
- 25. (Withdrawn) The method of claim 24, wherein the substrate comprises a semiconductor device structure.
- 26. (Withdrawn) The method of claim 24, wherein the material comprises photoresist.
- 27. (Withdrawn) The method of claim 24, wherein the material comprises SARC material.
- 28. (Withdrawn) The method of claim 27, wherein the SARC material has been applied to a semiconductor device structure to minimize reflectivity variations during photolithographic patterning on the semiconductor device structure.
- 29. (Withdrawn) The method of claim 24, wherein said contacting is carried out for a time of from about 10 to about 45 minutes.
- 30. (Withdrawn) The method of claim 24, wherein said contacting is carried out at temperature in a range of from about 50°C to about 80°C.
- 31. (Withdrawn) The method of claim 24, wherein the composition is devoid of hydroxylamine therein.
- 32. (Withdrawn) The method of claim 24, wherein said ACC comprises (a).
- 33. (Withdrawn) The method of claim 32, wherein the composition comprises the following components:
 - 0.1 40.0 weight % organic quaternary base;
 - 0.01-5 weight % alkali or alkaline earth base;
 - 0-80 weight % solvent(s) and/or amine(s);

- 0-5 weight % surfactant;
- 0 10 weight % chelator/passivation agent; and
- 0 98 weight % water,

wherein percentages of the components are percentages by weight, based on total weight of the composition, and wherein the total of the weight percentages of such components of the composition does not exceed 100 weight %.

- 34. (Withdrawn) The method of claim 24, wherein the composition includes at least one additional ingredient selected from the group consisting of stabilizers, dispersants, anti-oxidants, fillers, penetration agents, adjuvants, additives, fillers, and excipients.
- 35. (Withdrawn) The method of claim 32, wherein the composition comprises the following components:
 - 2-15 weight % organic quaternary base;
 - ~0.01-2 weight % alkali or alkaline earth base;
 - 0-50 weight % solvent(s) and/or amine(s);
 - ~0.01-2 weight % surfactant;
 - 0-5 weight % chelator/passivation agent; and
 - 40 95 weight % water,

wherein percentages of the components are percentages by weight, based on total weight of the composition, and wherein the total of the weight percentages of such components of the composition does not exceed 100 weight %.

36. (Withdrawn) A method of removing photoresist and/or SARC material from a substrate having said material thereon, said method comprising contacting the substrate with a cleaning composition for sufficient time to at least partially remove said material from the substrate, wherein the cleaning composition is selected from the group consisting of Formulations A-C², wherein all percentages are by weight, based on the total weight of the formulation:

Formulation A

- 5.36% benzyltrimethylammonium hydroxide
- 0.28% potassium hydroxide
- 3.0% 4-methylkmorpholine N-oxide
- 0.30% polyoxyethylene(150) dinonylphenyl ether
- 0.08% 2-mercaptobenzimidazole
- 91.0% water

Formulation B

5.36% benzyltrimethylammonium hydroxide

0.28% potassium hydroxide

3.0% 4-methylmorpholine N-oxide

0.30% polyoxyethylene(150) dinonylphenyl ether

0.20% 5-amino-1,3,4-thiadiazole-2-thiol

90.86% water

Formulation C

3.60% benzyltrimethylammonium hydroxide

0.27% potassium hydroxide

3.5% 4-methylmorpholine N-oxide

15.0% 4-(3-aminopropyl)morpholine

0.30% polyoxyethylene(150) dinonylphenyl ether

0.08% 2-mercaptobenzimidazole

77.25% water

Formulation D

5.36% benzyltrimethylammonium hydroxide

0.28% potassium hydroxide

20.0% dimethyl sulfoxide

0.08% 2-mercaptobenzimidazole

74.28% water

Formulation E

5.36% benzyltrimethylammonium hydroxide

0.28% potassium hydroxide

10.0% tetramethylene sulfone

0.30% oxirane, methyl-, polymer with oxirane, ether with 2,2'-(oxidoimino)bis(ethanol) (2:1), N(-3(C9-11-isoalkyloxy)propyl)derivatives, C₁₀-rich

0.08% 2-mercaptobenzimidazole

83.98% water

Formulation F

5.36% benzyltrimethylammonium hydroxide

0.28% potassium hydroxide

10.0% di(ethyleneglycol)butyl ether

10.0% 2-(2-dimethylamino)ethoxy)ethanol

0.30% oxirane, methyl-, polymer with oxirane, ether with 2,2'-(oxidoimino)bis(ethanol) (2:1), N(-3(C9-11-isoalkyloxy)propyl)derivatives, C₁₀-rich

74.06% water

Formulation G

5.36% benzyltrimethylammonium hydroxide

0.28% potassium hydroxide 10.0% tetramethylene sulfone 10.0% di(ethyleneglycol)butyl ether 0.10% oxirane, methyl-, polymer with oxirane, mono(octylphenyl)ether 0.08% 2-mercaptobenzimidazole 74.18% water,	
Formulation H	
benzyltrimethylammonium hydroxide, 40% aqueous solution potassium hydroxide, 45% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	9.0 % 0.6 % 7.0 % 4.3 % 0.1 % 20.0 % 59.02 %
Formulation I	
benzyltrimethylammonium hydroxide, 40% aqueous solution potassium hydroxide, 45% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	9.0 % 0.6 % 7.0 % 4.3 % 0.1 % 15.0 % 64.02 %
Formulation J	
benzyltrimethylammonium hydroxide, 40% aqueous solution potassium hydroxide, 45% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	9.0 % 0.6 % 7.0 % 4.3 % 0.1 % 10.0 % 69.02 %
Formulation K	
benzyltrimethylammonium hydroxide, 40% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	13.4 % 7.0 % 0.6 % 0.08 % 0.3 % 78.62 %
Formulation L	
benzyltrimethylammonium hydroxide, 40% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution	13.4 % 7.0 % 1.2 %

2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	0.08 % 0.3 % 78.02 %
Formulation M	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	5.85 % 7.0 % 1.2 % 0.08 % 0.3 % 85.57 %
Formulation N	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	2.93 % 7.0 % 1.2 % 0.08 % 0.3 % 88.49 %
Formulation O	
benzyltrimethylammonium hydroxide, 40% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	7.2 % 7.0 % 0.6 % 0.08 % 0.3 % 84.82 %
Formulation P	
benzyltrimethylammonium hydroxide, 40% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	3.6 % 7.0 % 1.2 % 0.08 % 0.3 % 87.82 %
Formulation Q	
benzyltrimethylammonium hydroxide, 40% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	3.6 % 7.0 % 0.6 % 0.08 % 0.3 % 88.42 %

Formulation R

benzyltrimethylammonium hydroxide, 40% aqueous solution N-methylmorpholine oxide, 50% aqueous solution KOH, 45% aqueous solution 2-mercaptobenzimidizole dinonylphenol polyoxyethylene water	7.2 % 7.0 % 0.3 % 0.08 % 0.3 % 85.12 %,
Formulation S	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) 3-amino-5-mercapto-1,2,4-triazole water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation T	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) 4-methyl-2-phenyl-imidazole water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation U	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) 2-mercaptothiazoline water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation V	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) 8-hydroxyquinoline water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation W	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine	22.26 % 0.6 % 0.08 % 2.33 %

phosphoric acid (86 %) 1-phenyl-2-tetrazoline-5-thione water	1.69 % 1.0 % 72.04 %
Formulation X	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) gallic acid water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation Y	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) salicylic acid water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation Z	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole methyldiethanolamine phosphoric acid (86 %) ascorbic acid water	22.26 % 0.6 % 0.08 % 2.33 % 1.69 % 1.0 % 72.04 %
Formulation A ²	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole aminopropyl morpholine 4-methyl-2-phenyl-imidazole water	7.2 % 0.6 % 0.08 % 10 % 1.0 % 81.12 %
Formulation B ²	
benzyltrimethylammonium hydroxide, 40% aqueous solution Potassium hydroxide, 45% aqueous solution 2-mercaptobenzimidazole aminopropyl morpholine 4-methyl-2-phenyl-imidazole water	7.2 % 0.6 % 0.08 % 10 % 0.5 % 81.62 %

Formulation C²

benzyltrimethylammonium hydroxide, 40% aqueous solution	7.2 %
Potassium hydroxide, 45% aqueous solution	0.6 %
2-mercaptobenzimidazole	0.08 %
aminopropyl morpholine	10 %
4-methyl-2-phenyl-imidazole	1.0 %
water	81.02 %
dinonylphenol polyoxyethylene	0.1 %.

- 37. (Withdrawn) The method of claim 24, wherein said ACC comprises (b).
- 38. (Withdrawn) The method of claim 37, wherein the cleaning composition includes an aqueous solution of at least one oxidant, a strong base, optionally a chelator and optionally a cosolvent and/or a surfactant.
- 39. (Withdrawn) The method of claim 24, wherein the ACC comprises potassium hydroxide.
- 40. (Withdrawn) The method of claim 37, wherein the cleaning composition includes the following components:

0.1-30 wt % strong base;

0.01-30 wt % oxidant;

0-10 wt % chelator;

0-5 wt % surfactant;

0-50 wt % co-solvent; and

20-98.9 wt % deionized water,

wherein percentages of the components are percentages by weight, based on total weight of the composition, and wherein the total of the weight percentages of such components of the composition does not exceed 100 weight %.

- 41. (Withdrawn) The method of claim 40, wherein the strong base comprises a base species selected from the group consisting of potassium hydroxide and alkylammonium hydroxides and choline hydroxide.
- 42. (Withdrawn) The method of claim 37, wherein the oxidant comprises an oxidant species selected from the group consisting of hydrogen peroxide, amine-N-oxides, perborate salts, persulfate salts, and combinations of two or more of the foregoing.

- 43. (Withdrawn) The method of claim 24, wherein the cleaning composition further comprises a chelator.
- 44. (Withdrawn) The method of claim 43, wherein the chelator comprises a chelator species selected from the group consisting of: triazoles; triazoles substituted with substituent(s) selected from the group consisting of C₁-C₈ alkyl, amino, thiol, mercapto, imino, carboxy and nitro; thiazoles; tetrazoles; imidazoles; phosphates; thiols; azines; glycerols; amino acids; carboxylic acids; alcohols; amides; and quinolines.
- (Withdrawn) The method of claim 43, wherein the chelator comprises a chelator species 45. selected from the group consisting of: 1,2,4-triazole; benzotriazole; tolyltriazole; 5-phenylbenzotriazole; 5-nitro-benzotriazole; 1-amino-1,2,4-triazole; hydroxybenzotriazole; 2-(5-aminopentyl)-benzotriazole; 1-amino-1,2,3-triazole; 1-amino-5-methyl-1,2,3-triazole; 3-amino-1,2,4triazole; 3-mercapto-1,2,4-triazole; 3-isopropyl-1,2,4-triazole; 5-phenylthiol-benzotriazole; halobenzotriazoles wherein halo is selected from the group consisting of F, Cl, Br and I; naphthotriazole; 2-mercaptobenzoimidizole; 2-mercaptobenzothiazole; 5-aminotetrazole; 5amino-1,3,4-thiadiazole-2-thiol; 2,4-diamino-6-methyl-1,3,5-triazine; triazine; thiazole; methyltetrazole; 1,3-dimethyl-2-imidazolidinone; 1,5-pentamethylenetetrazole; 1-phenyl-5diaminomethyltriazine; mercaptobenzothiazole; imidazoline thione: mercaptotetrazole; mercaptobenzimidazole; 4-methyl-4H-1,2,4-triazole-3-thiol; 5-amino-1,3,4-thiadiazole-2-thiol; benzothiazole; trritolyl phosphate; indiazole; guanine; adenine; glycerol; thioglycerol; nitrilotriacetic acid; salicylamide; iminodiacetic acid; benzoguanamine; melamine; thiocyranuric acid; anthranilic acid; 8-hydroxyquinoline; 5-carboxylic acid-benzotriazole; 3-mercaptopropanol; boric acid; and iminodiacetic acid.
- 46. (Withdrawn) The method of claim 24, wherein the cleaning composition further comprises a surfactant.
- 47. (Withdrawn) The method of claim 46, wherein the surfactant comprises a surfactant species selected from the group consisting of: fluoroalkyl surfactants; polyethylene glycols; polypropylene glycols; polyethylene glycol ethers; polypropylene glycol ethers; carboxylic acid salts; dodecylbenzenesulfonic acid and salts thereof; polyacrylate polymers; dinonylphenyl polyoxyethylene; silicone polymers; modified silicone polymers; acetylenic diols; modified acetylenic diols, alkylammonium salts; modified alkylammonium salts; and combinations of two

or more of the foregoing.

- 48. (Withdrawn) The method of claim 24, wherein the cleaning composition further comprises a co-solvent.
- 49. (Withdrawn) The method of claim 48, wherein the co-solvent comprises a co-solvent species selected from the group consisting of: amines; glycols; glycol ethers; polyglycol ethers; and combinations of two or more of the foregoing.
- (Withdrawn) The method of claim 48, wherein the co-solvent comprises a co-solvent 50. consisting of: dimethyldiglycolamine; species selected from the group diazabicyclo[5.4.0]undecene; aminopropylmorpholine; triethanolamine; methylethanolamine; diethylene glycol; propylene glycol; neopentyl glycol; hydroxyethylmorpholine; aminopropylmorpholine; di(ethylene glycol)monoethyl ether; di(propylene glycol)propyl ether; ethylene glycol phenyl ether; di(propylene glycol) butyl ether; butyl carbitol; polyglycol ethers; and combinations of two or more of the foregoing.
- 51. (Withdrawn) The method of claim 37, wherein the composition includes:
- 0.1-30 wt % strong base
- 2-30 wt % oxidant
- 0-10 wt % chelator
- 0-5 wt % surfactant
- 20-98 wt % deionized water

wherein percentages of the components are percentages by weight, based on total weight of the composition, and wherein the total of the weight percentages of such components of the composition does not exceed 100 weight %.

52. (Withdrawn) The method of claim 24, wherein the cleaning composition is selected from the group consisting of Formulations D^2 - R^2 , wherein all percentages are by weight, based on the total weight of the formulation:

Formulation D²

tetramethylammonium hydroxide, 25% aqueous solution	14.7 %
N-methylmorpholine oxide, 50% aqueous solution	7.0 %
dinonylphenol ethoxylate, 7% aqueous solution	4.3 %

3-amino-5-mercapto-1,2,4-triazole water	0.1 % 73.9 %
Formulation E ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution ammonium tetrathiomolybdate water	14.7 % 7.0 % 4.3 % 0.1 % 73.9 %
Formulation F ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	14.7 % 7.0 % 4.3 % 0.1 % 20.0 % 53.9 %
Formulation G ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole N-ethylmorpholine water	14.7 % 7.0 % 4.3 % 0.1 % 20.0 % 53.9 %
Formulation H ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminoethylpiperidine water	14.7 % 7.0 % 4.3 % 0.1 % 20.0 % 53.9 %
Formulation I ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 3-amino-5-1,2,4-triazole aminopropylmorpholine water	14.7 % 7.0 % 4.3 % 0.1 % 20.0 % 53.9 %
Formulation J ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution	14.7 % 7.0 %

dinonylphenol ethoxylate, 7% aqueous solution 3-amino-5-1,2,4-triazole aminopropylmorpholine water	4.3 % 0.1 % 10.0 % 63.9 %
Formulation K ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	14.7 % 7.0 % 4.3 % 0.1 % 20.0 % 53.9 %
Formulation L ²	
tetramethylammonium hydroxide, 25% aqueous solution N-methylmorpholine oxide, 50% aqueous solution dinonylphenol ethoxylate, 7% aqueous solution 2-mercaptobenzimidazole aminopropylmorpholine water	14.7 % 7.0 % 4.3 % 0.1 % 10.0 % 63.9 %
Formulation M ²	
tetramethylammonium hydroxide, 25% aqueous solution hydrogen peroxide, 30% aqueous solution 5-aminotetrazole water	4.0 % 2.0 % 0.1 % 93.9 %
Formulation N ²	
tetramethylammonium hydroxide, 25% aqueous solution hydrogen peroxide, 30% aqueous solution 2,4-diamino-6-methyl-1,3,5-triazine water	4.0 % 2.0 % 0.1 % 93.9 %
Formulation O ²	
tetramethylammonium hydroxide, 25% aqueous solution hydrogen peroxide, 30% aqueous solution 5-amino-1,3,4-thiadiazole-2-thiol water	4.0 % 2.0 % 0.1 % 93.9 %
Formulation P ²	
tetramethylammonium hydroxide, 25% aqueous solution hydrogen peroxide, 30% aqueous solution 1,2,4-triazole water	4.0 % 2.0 % 0.1 % 93.9 %

Formulation Q²

tetramethylammonium hydroxide, 25% aqueous solution	4.0 %
hydrogen peroxide, 30% aqueous solution	2.0 %
2,4-dihydroxy-6-methylpyrimidine	0.1 %
water	93.9 %

Formulation R²

tetramethylammonium hydroxide, 25% aqueous solution	4.0 %
hydrogen peroxide, 30% aqueous solution	2.0 %
8-hydroxyquinoline	0.1 %
water	93.9 %.

- 53. (Previously Presented) The cleaning composition of claim 1, wherein the quaternary base comprises an organic quaternary ammonium base.
- 54. (Previously Presented) The cleaning composition of claim 1, wherein the quaternary base comprises benzyltrimethylammonium hydroxide.
- 55. (Previously Presented) The cleaning composition of claim 1, wherein the ACC comprises benzyltrimethylammonium hydroxide and potassium hydroxide.
- 56. (Previously Presented) The cleaning composition of claim 19, wherein the co-solvent comprises a glycol ether.
- 57. (Previously Presented) The cleaning composition of claim 1 comprising benzyltrimethylammonium hydroxide; potassium hydroxide; tetramethylene sulfone; di(ethyleneglycol)butyl ether; oxirane, methyl-, polymer with oxirane, mono(octylphenyl)ether; 2-mercaptobenzimidazole; and water.
- 58. (Previously Presented) A method of making a semiconductor device comprising contacting the substrate with the cleaning composition of claim 1 for sufficient time to at least partially remove said material from the substrate.
- 59. (Previously Presented) The method of claim 58, wherein the oxidant comprises an oxidant species selected from the group consisting of amine-N-oxides, perborate salts, persulfate salts, and combinations of two or more of the foregoing.